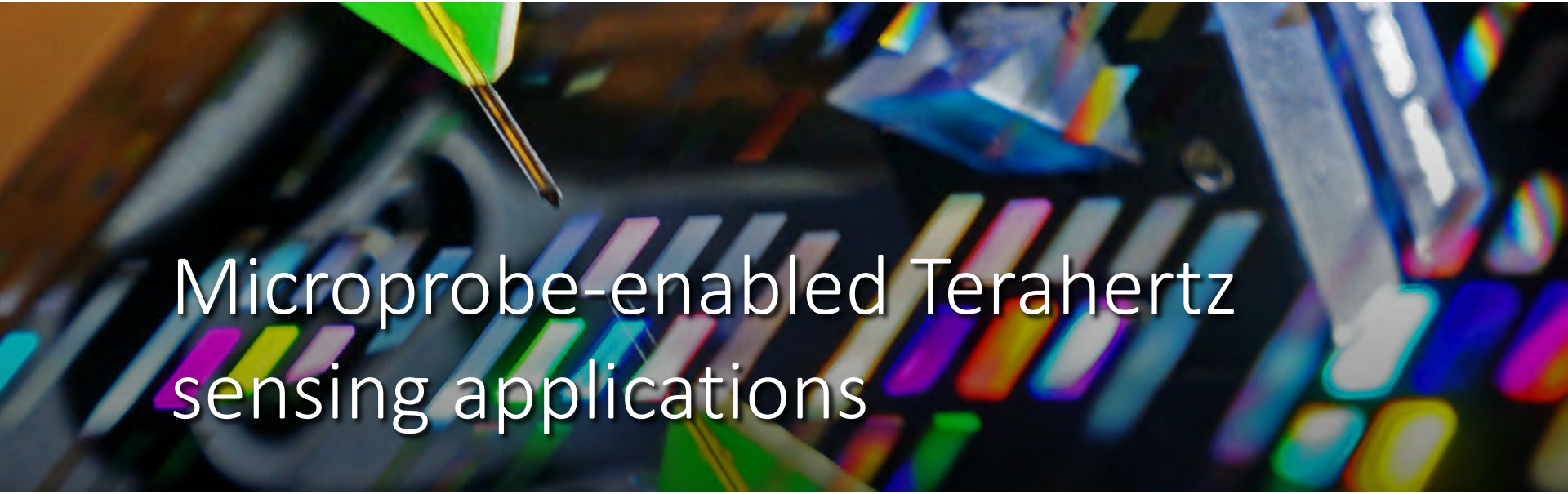


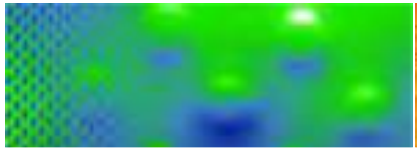
Microprobe-enabled Terahertz sensing applications

World of Photonics, Laser 2015, Munich

Protemics GmbH
Aachen, Germany

Terahertz microprobing technology:

Taking advantage of Terahertz range benefits without being compromised by wavelength-based resolution limitations.



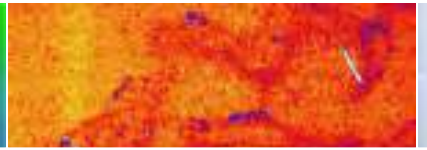
Terahertz Research

Application areas:

- Metamaterials
- Plasmonics
- Devices
- Waveguides
- Sensor surfaces
- Graphene

Benefits:

- Near-field access
- High-sensitivity
- Low-invasiveness
- Polarisation sensitive
- Broadband



Thin-film Analysis

Application areas:

- Solar cells
- Displays
- Flexible electronics
- Doping layers
- Graphene
- Transparent conductors

Benefits:

- Sheet resistance imaging
- Contactless
- Micron-scale resolution
- Large-area scanning
- High-speed scanning

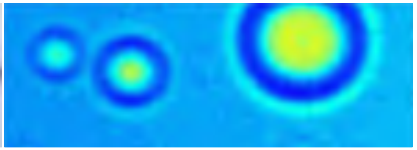
Chip-Testing

Application areas:

- Time-domain reflectometry
- Fault isolation
- Packaging level inspection
- 3D integration
- Through silicon via (TSV)

Benefits:

- Market leading TDR resolution
- Contactless
- Non-destructive
- Cost advantage



Volume Screening

Application areas:

- Plastic weld inspection
- Fiber inforced polymers
- Chip underfill inspection
- Organic layer screening

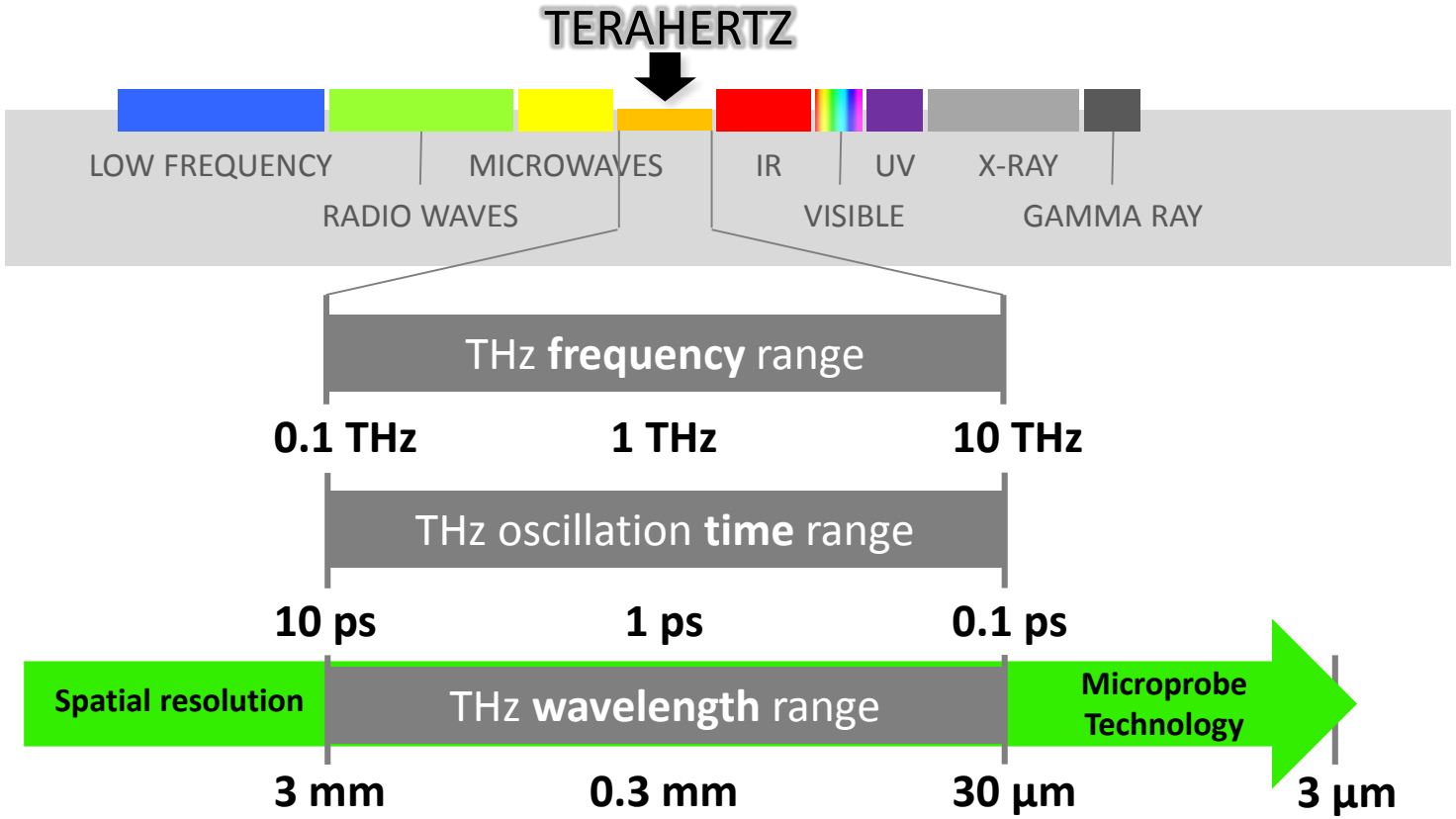
Benefits:

- Non-destructive
- Fast inspection
- Screening of opaque plastics
- Detection of microdefects

Outline

- **Introduction**
  - Mismatch between THz radiation wavelengths and micro/nanostructure size
- **THz microprobes**
  - Working principle
- **Thin-film analysis with sub-wavelength resolution on large areas**
  - Thin-film conductors (Metals, Graphene, Semiconductors, ITO and ITO-replacement materials)
- **THz Metamaterials**
  - THz-Metamaterials, Metamaterial-based sensing
- **Plastic laser weld inspection**
  - Near-field detection of micro-defects
- **THz device analysis**
  - THz on-chip device characterization
  - Failure localization in chip packages

Introduction



Introduction

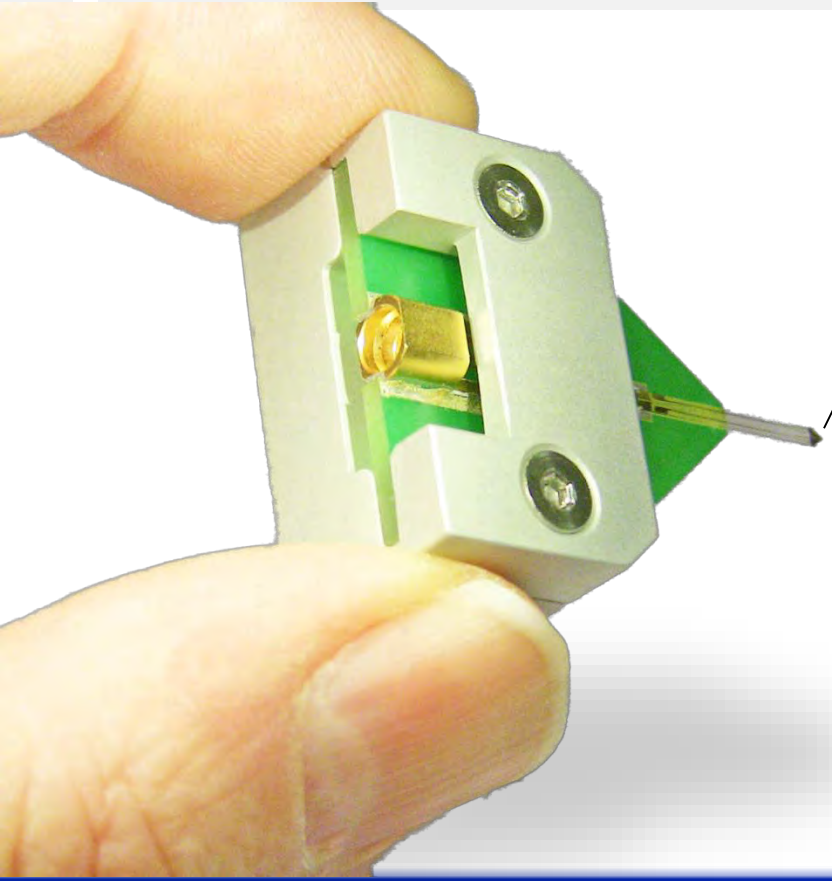
Large THz wavelengths are problematic:

- When structures under test are too small (similar to λ or even smaller)
  - Lateral Micro/Nanostructures (Solar cells, electronic structures, micro defects, …)
  - Only minute (pl) sample volumes available (-> biosensing)
- On signal transfer to or from THz field confining structures
  - Waveguides
  - Integrated devices

Solution:

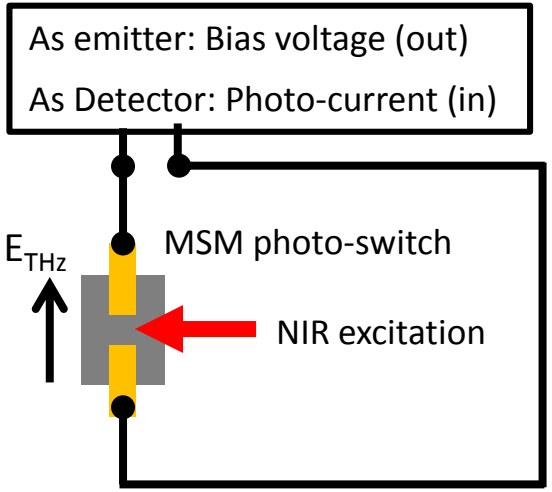
- Make THz emitter and/or detector smaller than the wavelength
- Bring the miniaturized emitter/detector in sub-wavelength distance to structure under test

THz micro-emitters/detectors

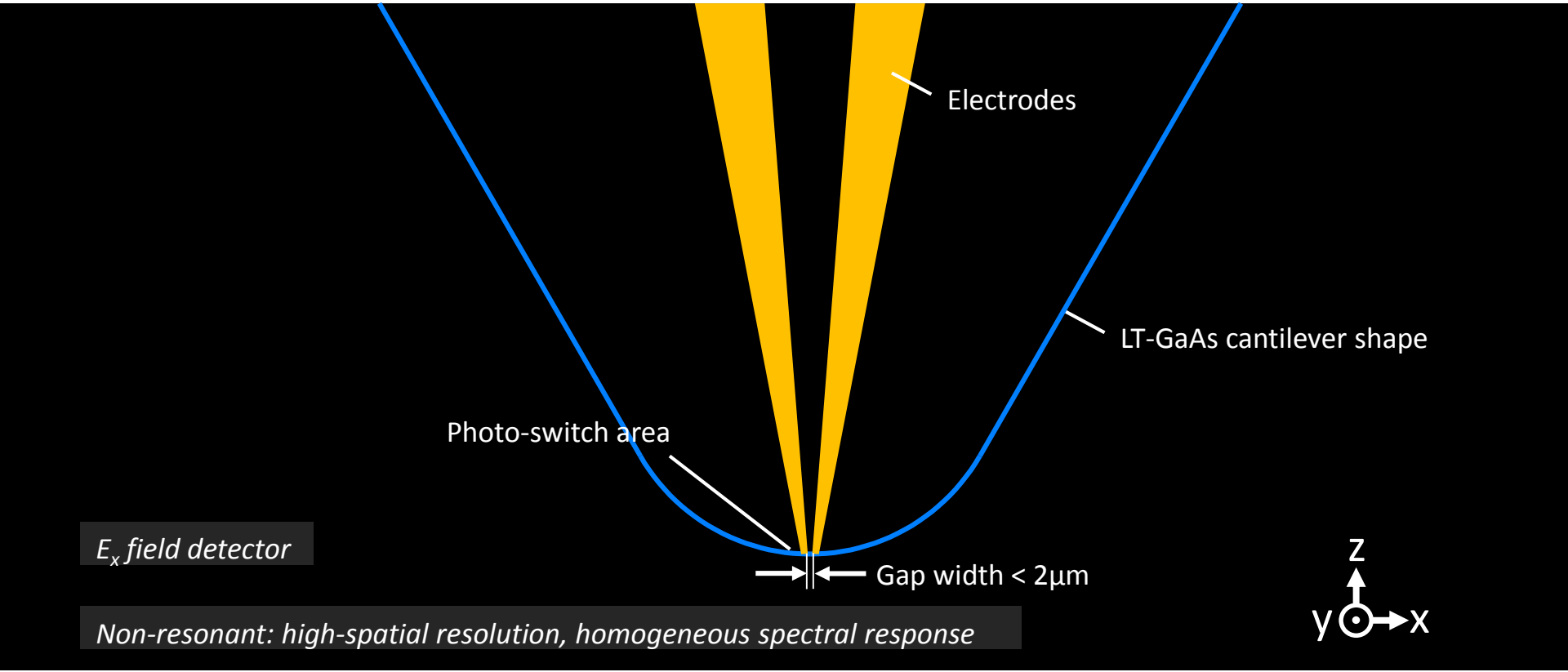


Active microstructure

Cantilever thickness = 1 µm



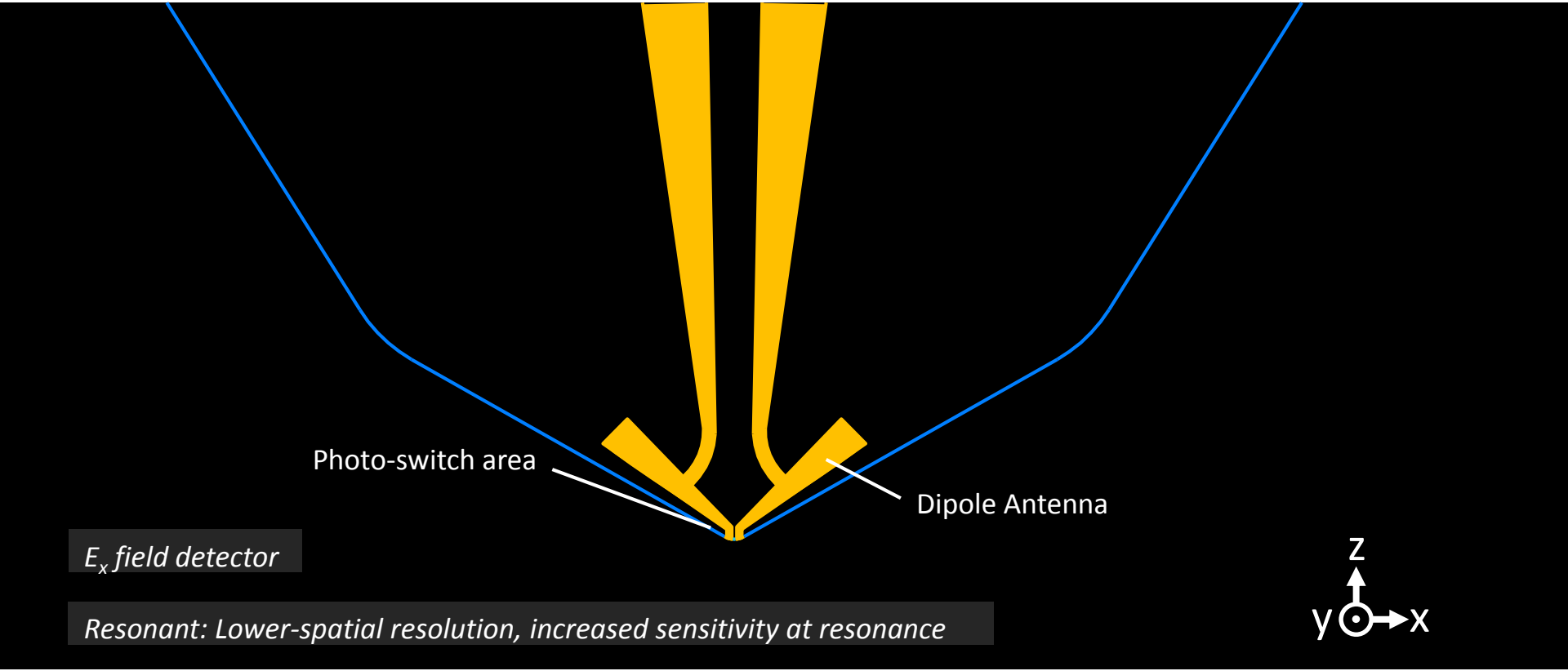
Application specific designs



E_x field detector

Non-resonant: high-spatial resolution, homogeneous spectral response

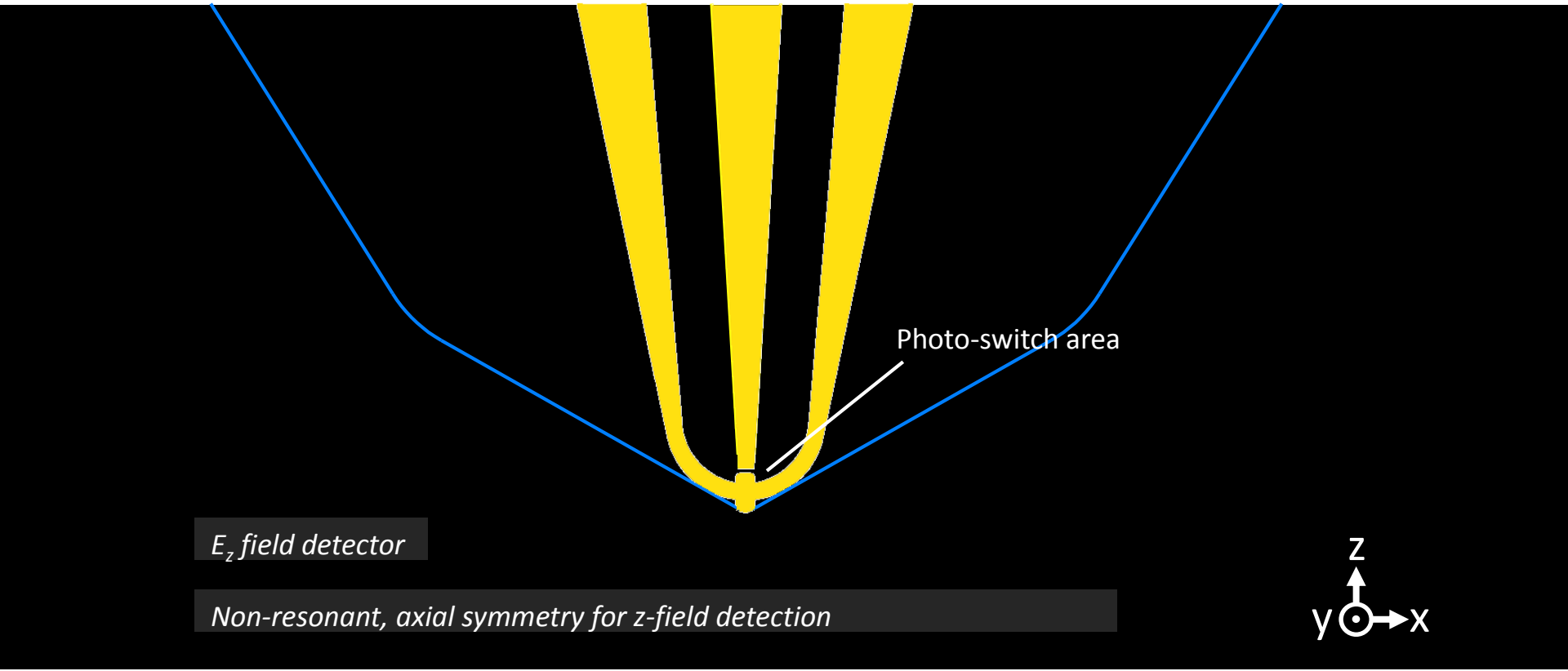
Application specific designs



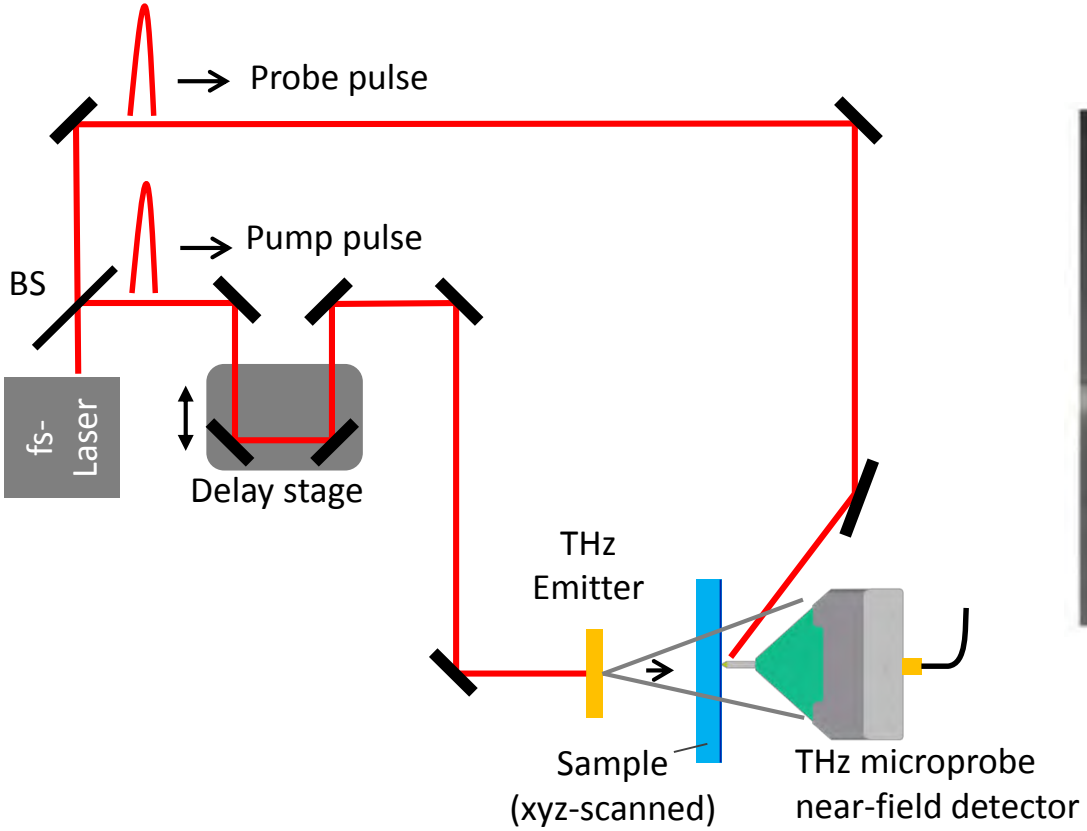
E_x field detector

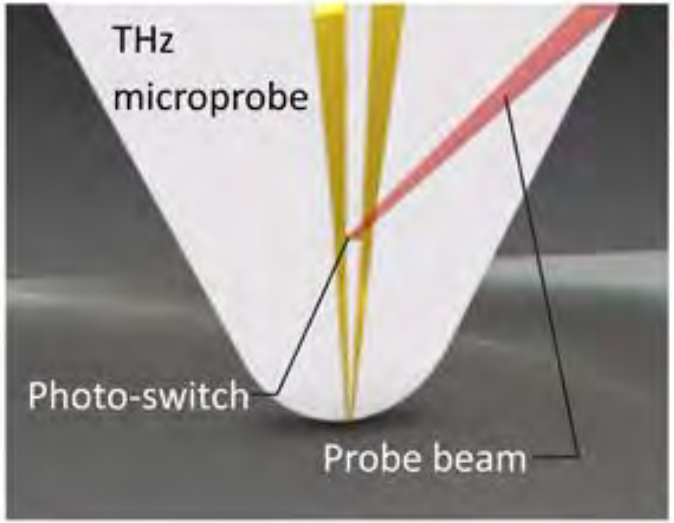
Resonant: Lower-spatial resolution, increased sensitivity at resonance

Application specific designs

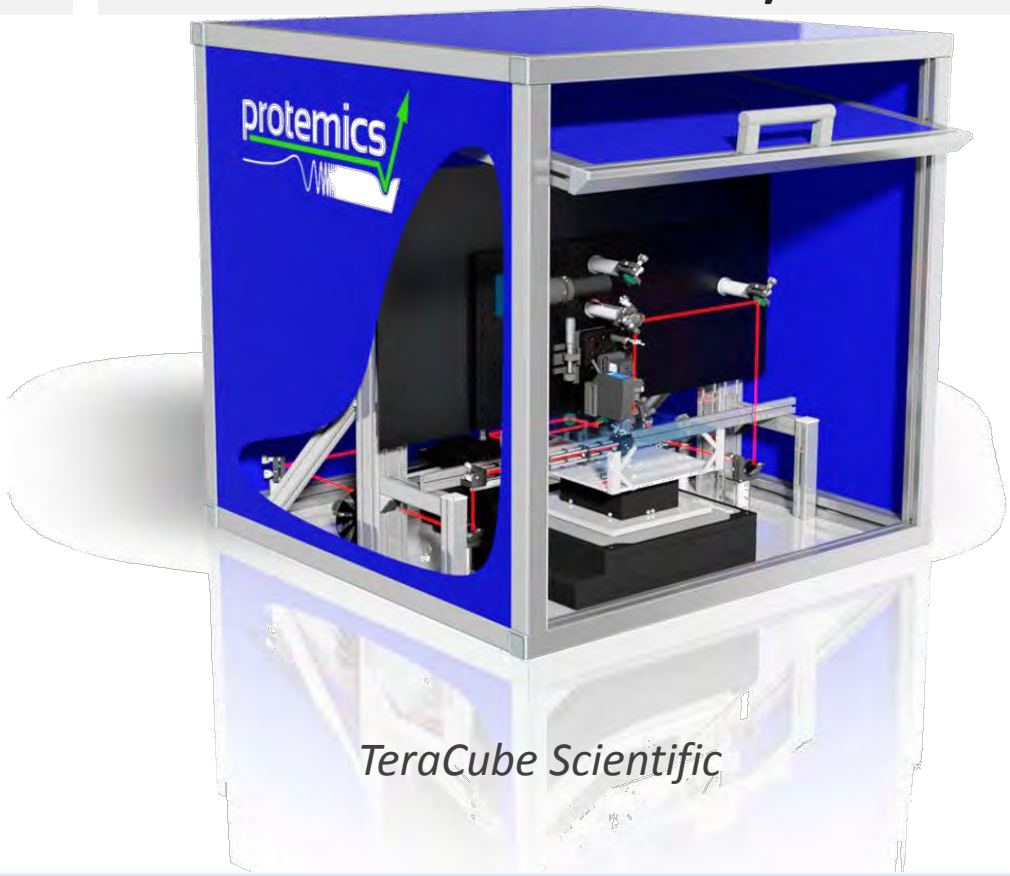


TD near-field sampling





TD near-field system

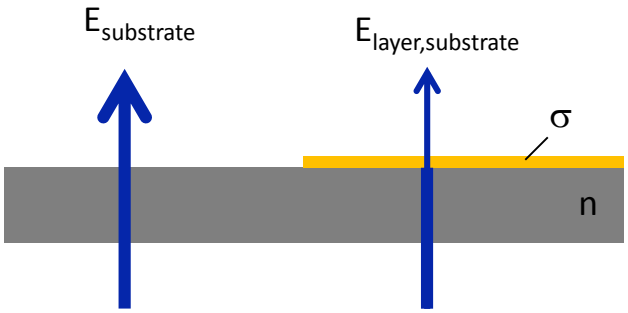


TeraCube Scientific

- **Automated table-top system**
  - 90x90x90 cm box including:
    - Laser
    - Scanning components
    - Opto-mechanics
    - Optics
    - Electronics
  - External components
    - PC
    - Supply unit

Thin-film conductors

- **Surface analysis with sub-wavelength resolution on large areas**
  - Sheet resistance imaging of thin-film conductors such as
    - Metals
    - Graphene
    - Doped semiconductors
    - Optically transparent conductors: ITO and ITO-replacement materials



Tinkham Formula:

$$\frac{E_{layer,substrate}(\omega)}{E_{substrate}(\omega)} = \frac{1+n}{1+n+Z_0\sigma(\omega)d}$$

Accessible sheet resistance range: 0.1 – 10000 Ohm

Thin-film conductors

Short-comings of state-of-the-art sheet-resistance measurement tools

Contact-based four-point probe measurements are problematic:

- On **large-bandgap** semiconductors (e.g. GaN or SiC)
  -> Imprecise measurements because of nonlinear contacts
- On **passivated** samples (e.g. Solar cells)
  -> No contact
- On **nanostructures** (e.g. metal mesh nanostructures)
  -> Requires formation of additional contact pads

- If measurement **time** matters
  -> Extremely time-consuming (5s/measurement point)
- If non-**destructive**ness matters
  -> Puncturing from contact needles

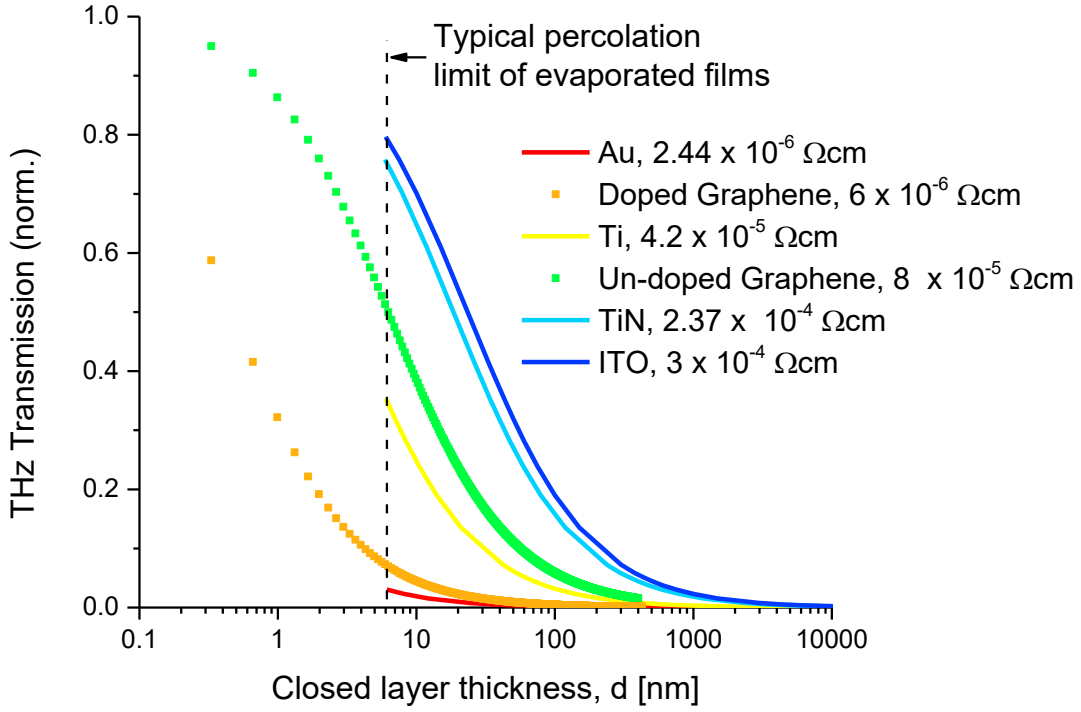
Thin-film conductors

Short-comings of the state-of-the-art sheet-resistance measurement tools

Non-contact Eddy current measurements:

- Spatial resolution is limited to 1 cm for **quantitative** measurements
- Spatial resolution is limited to 2 mm for **qualitative** measurements.

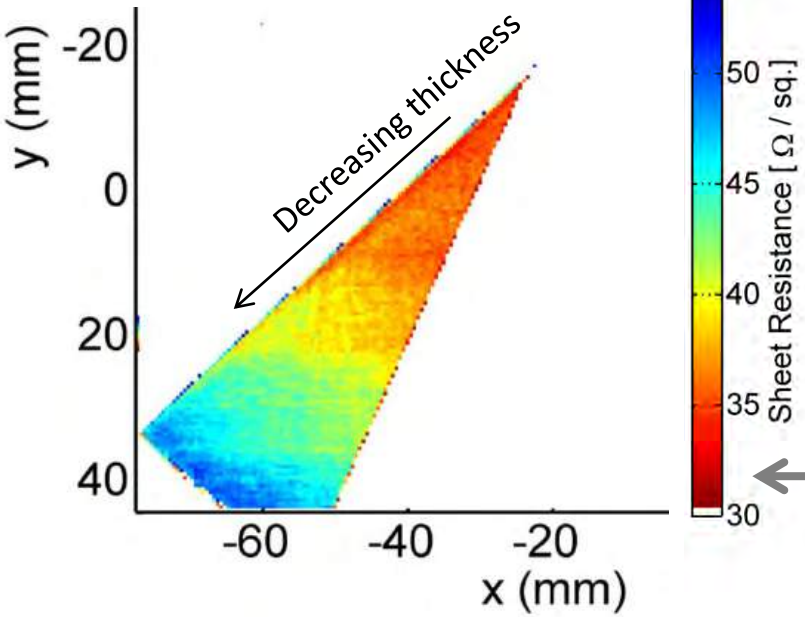
Thin-film conductors



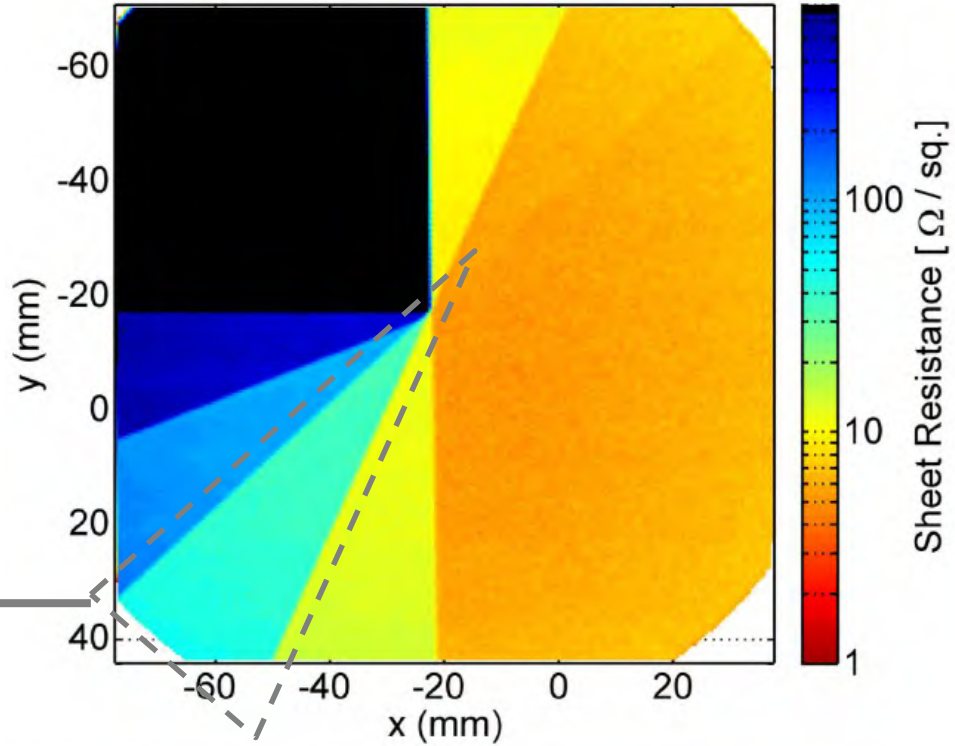
Substrate:
Silicon

Thin-film conductors

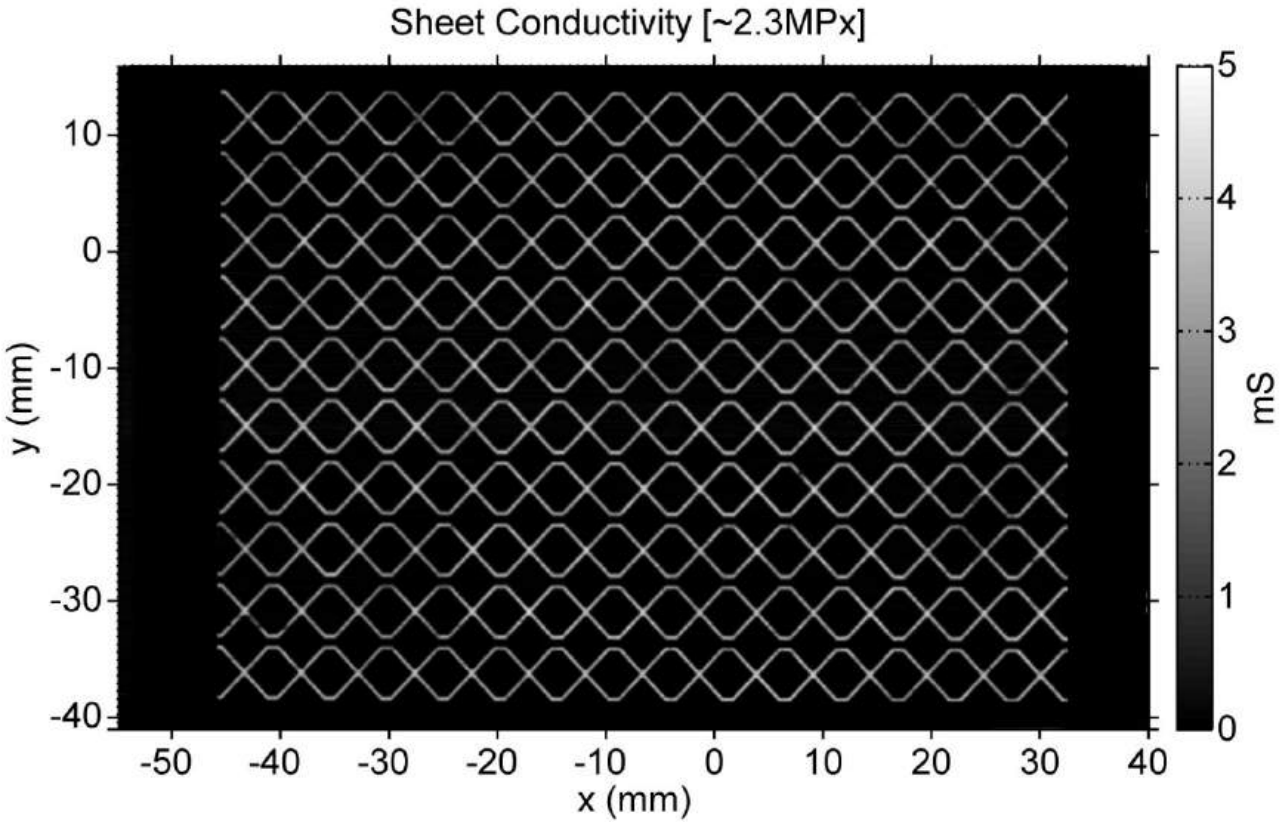
Example: Sputtered metal layers with varying thickness on glass



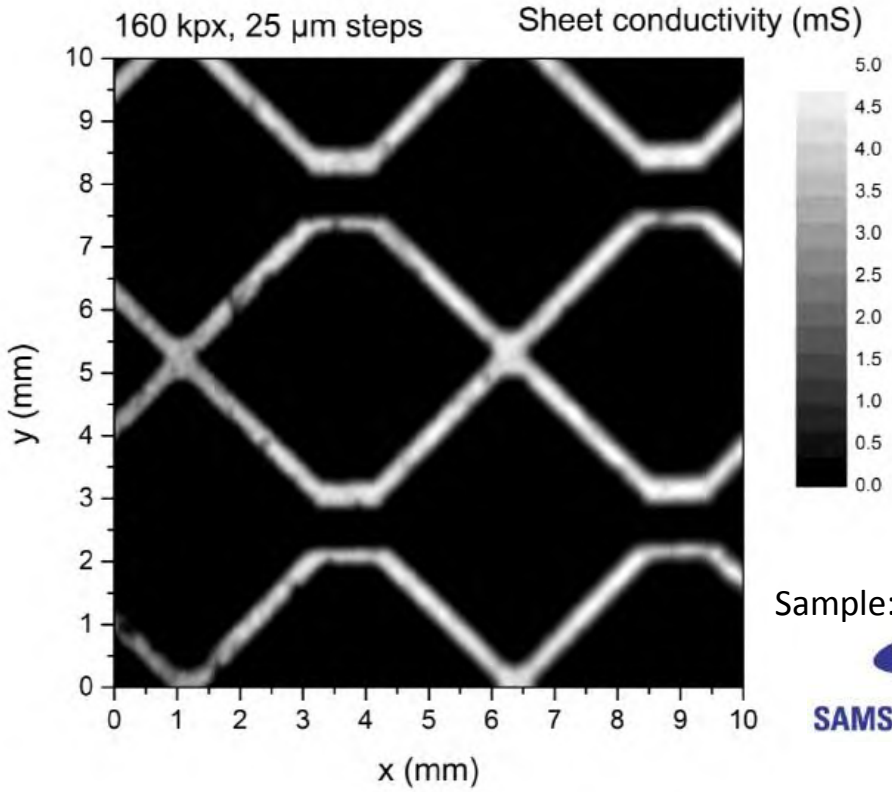
Measured with THz microprobe



Thin-film conductors: Graphene

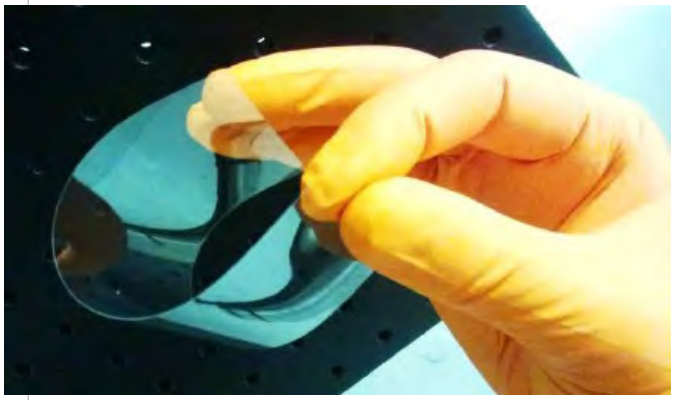


Thin-film conductors: Graphene



Sample:

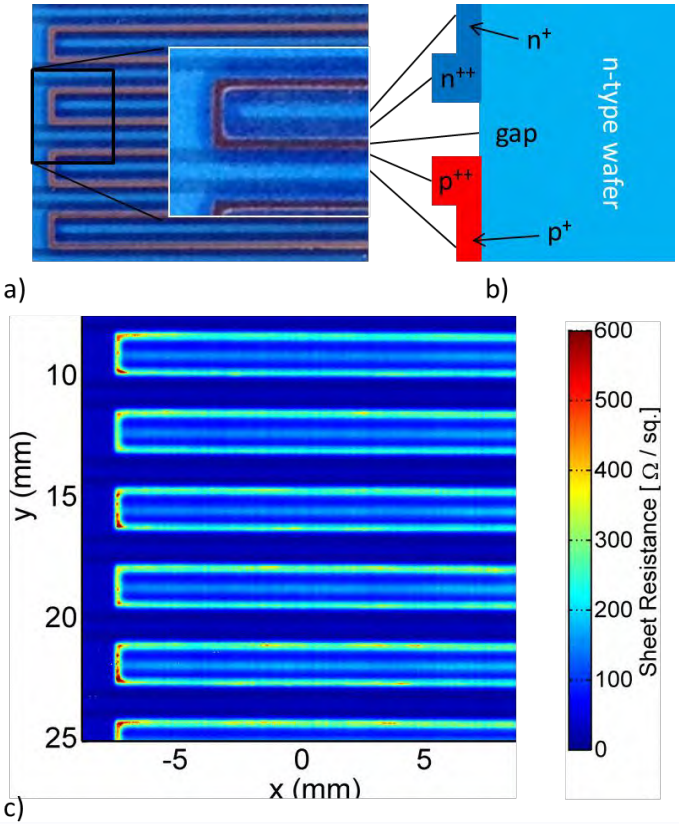
SAMSUNG TECHWIN



- Graphene pattern on PET foil
- Flexible display application

High-speed contactless raster scanning on **bended** surfaces

Thin-film conductors: Doped mc-Si

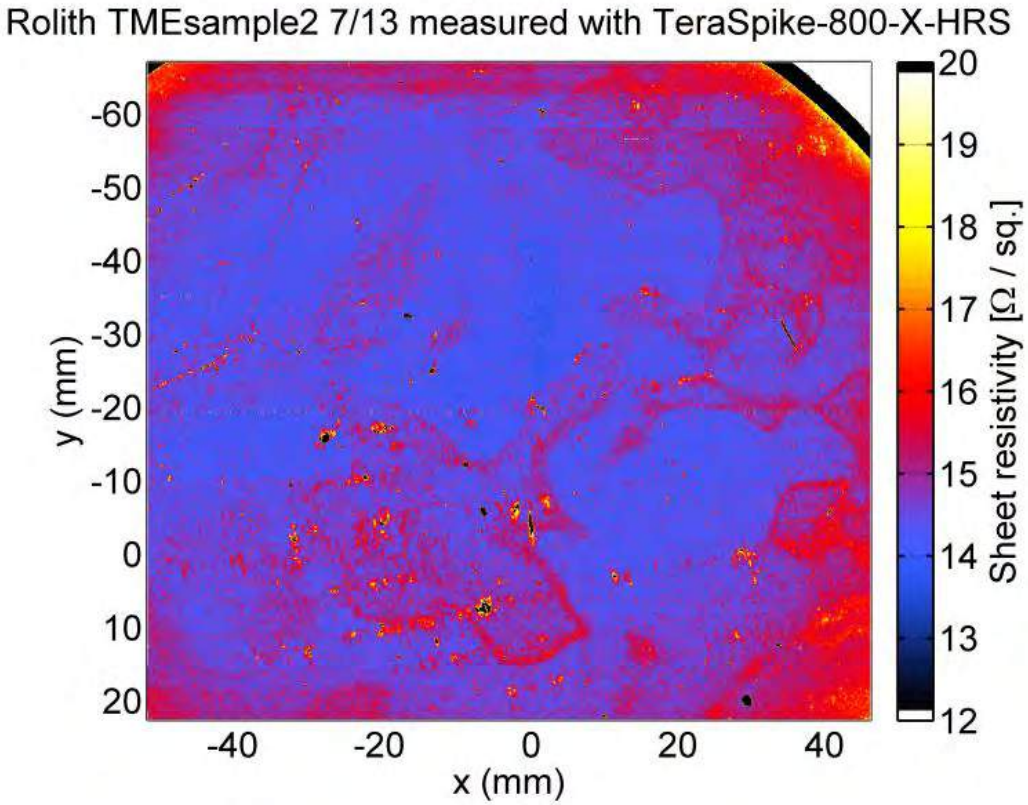


- IBC solar cell structure
- Laser-based material ablation process

- Sheet resistance image reveals areas of process induced inhomogenuity
- Applicable on full cell area and textured surfaces

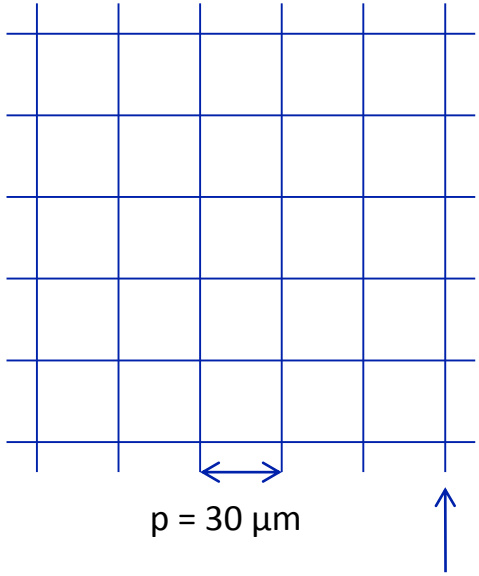
In collaboration with: ECN

Thin-film conductors: ITO-replacements



Sample:

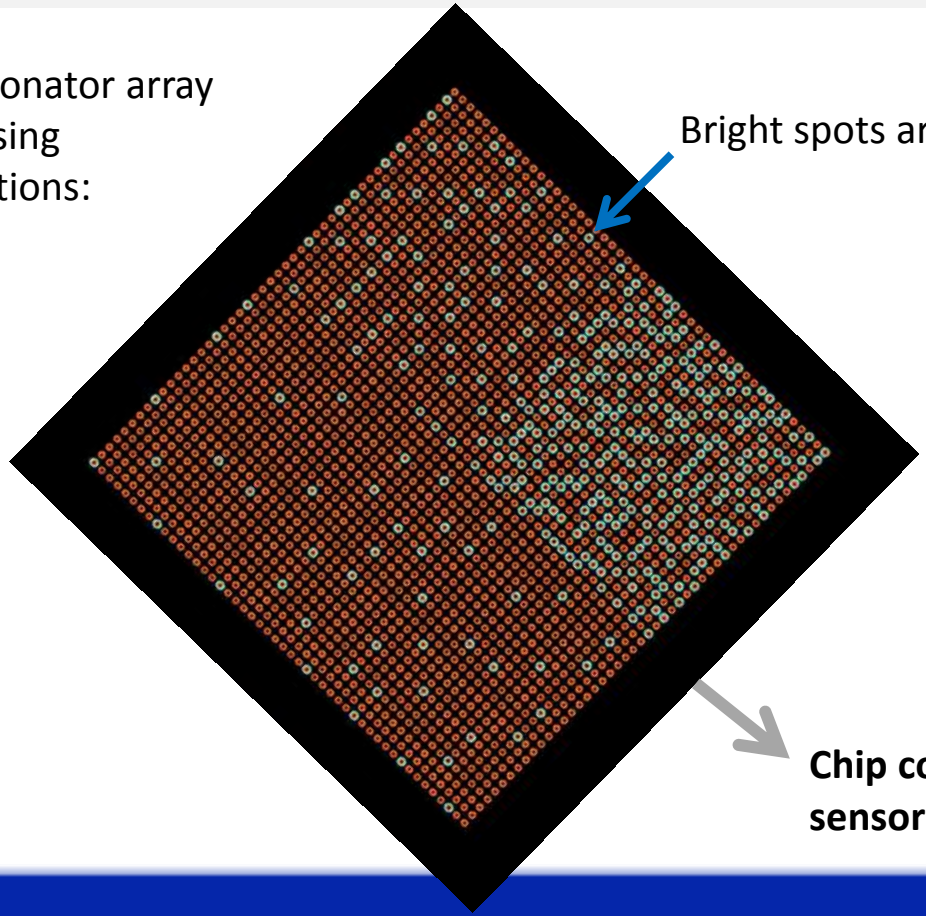
Al nanowire mesh on glass



Transparency > 94%

Metamaterials for sensing

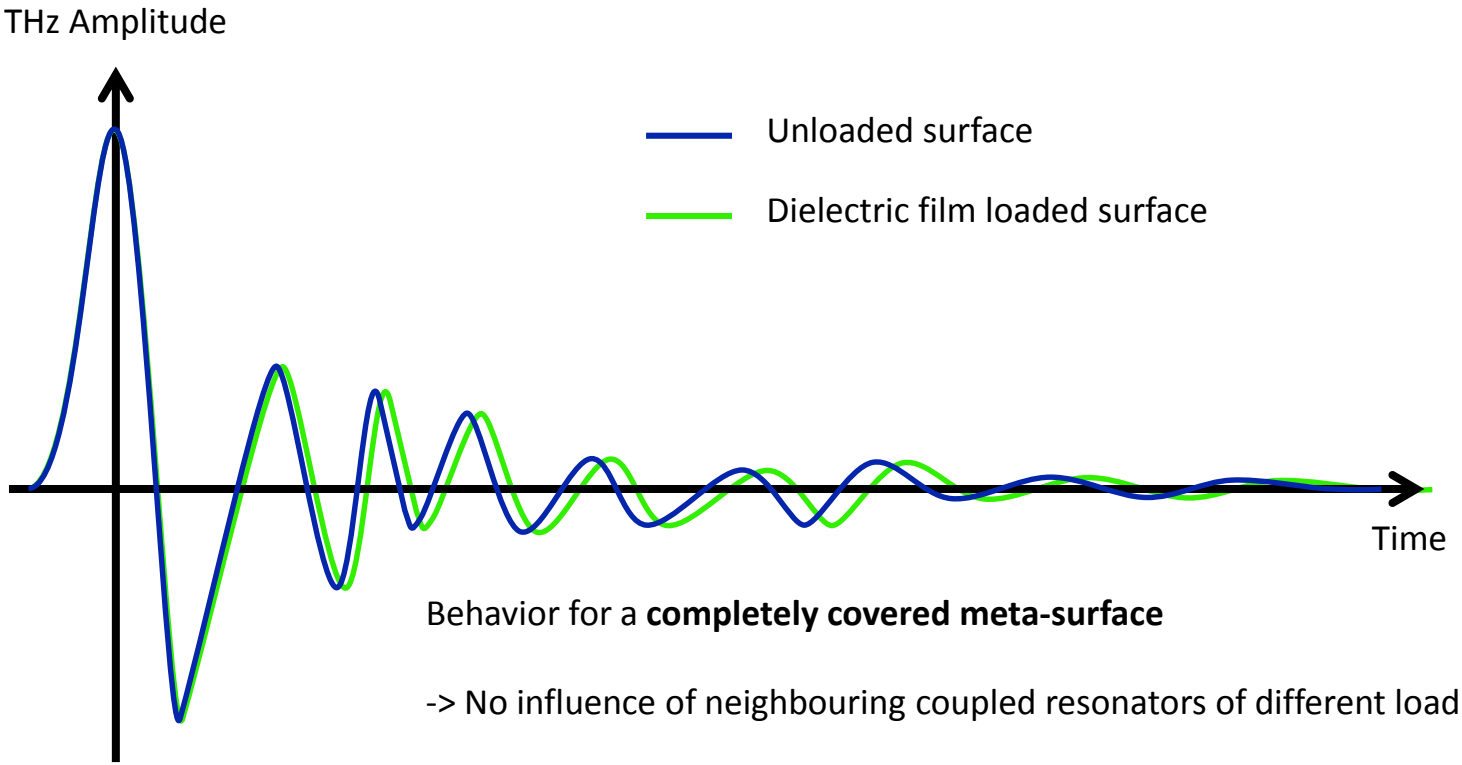
Ringresonator array for sensing applications:



Bright spots are dielectrically loaded

Chip contains 2304 sensor spots

Metamaterials for sensing

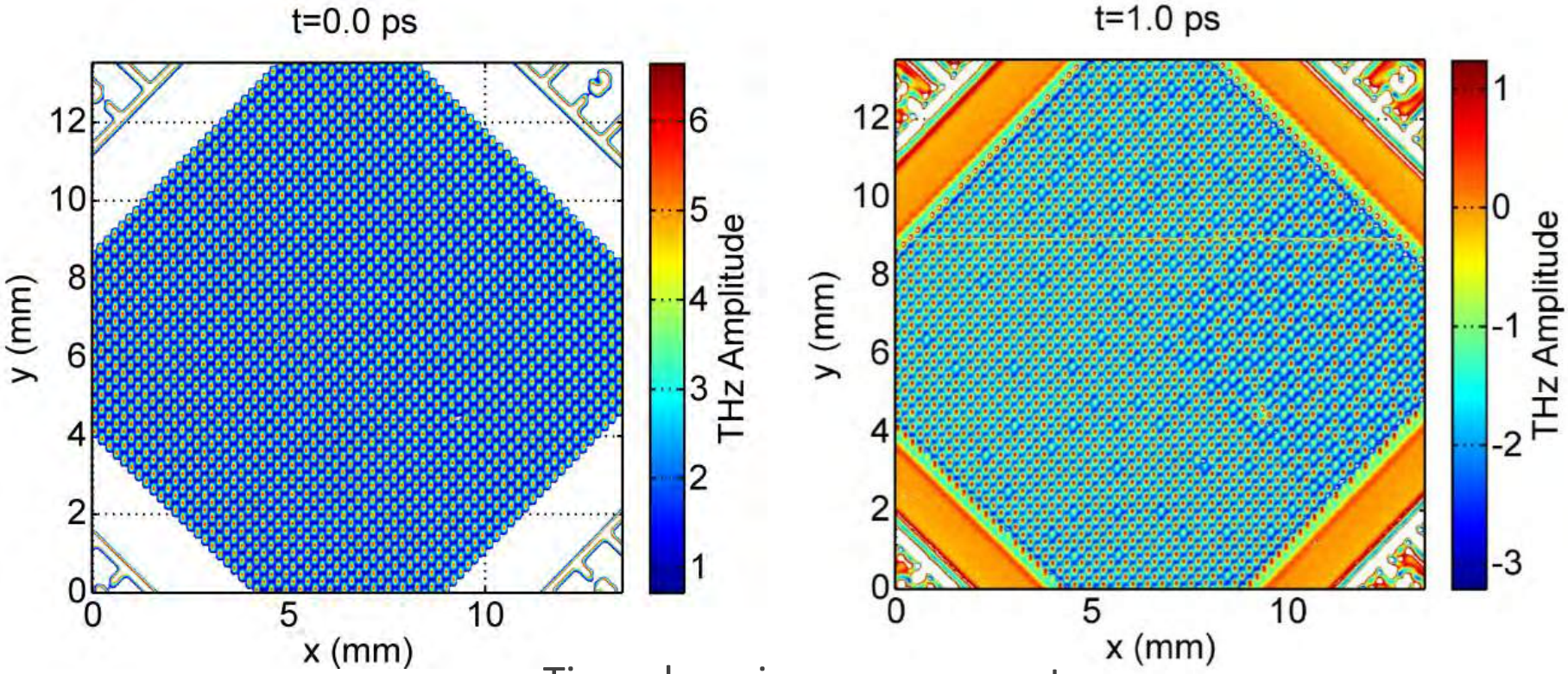


Behavior for a **completely covered meta-surface**

-> No influence of neighbouring coupled resonators of different loading state.

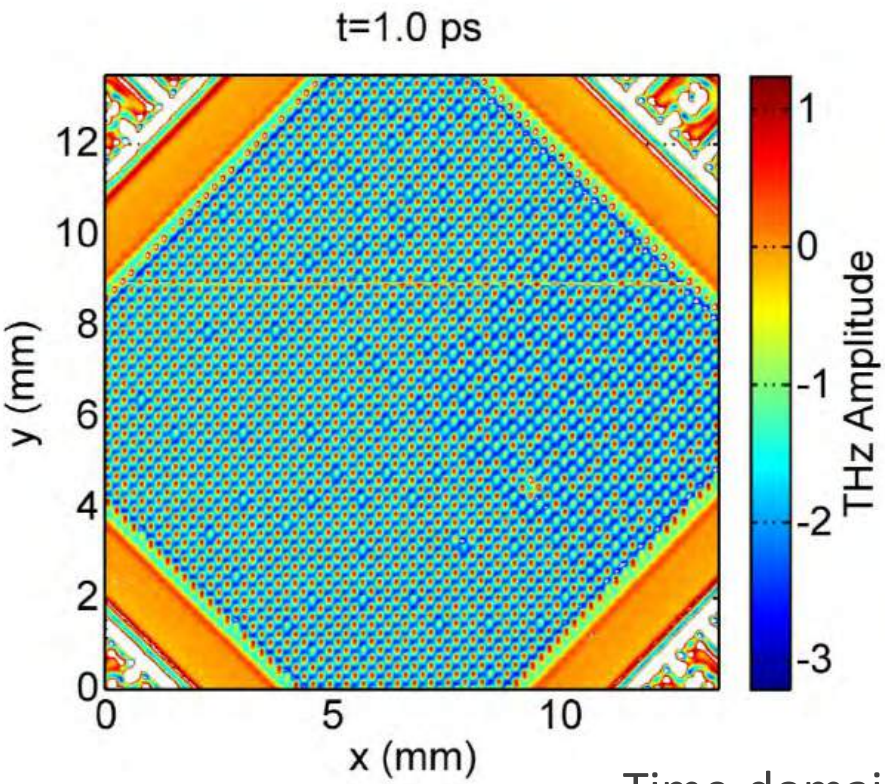
What about single element loading?

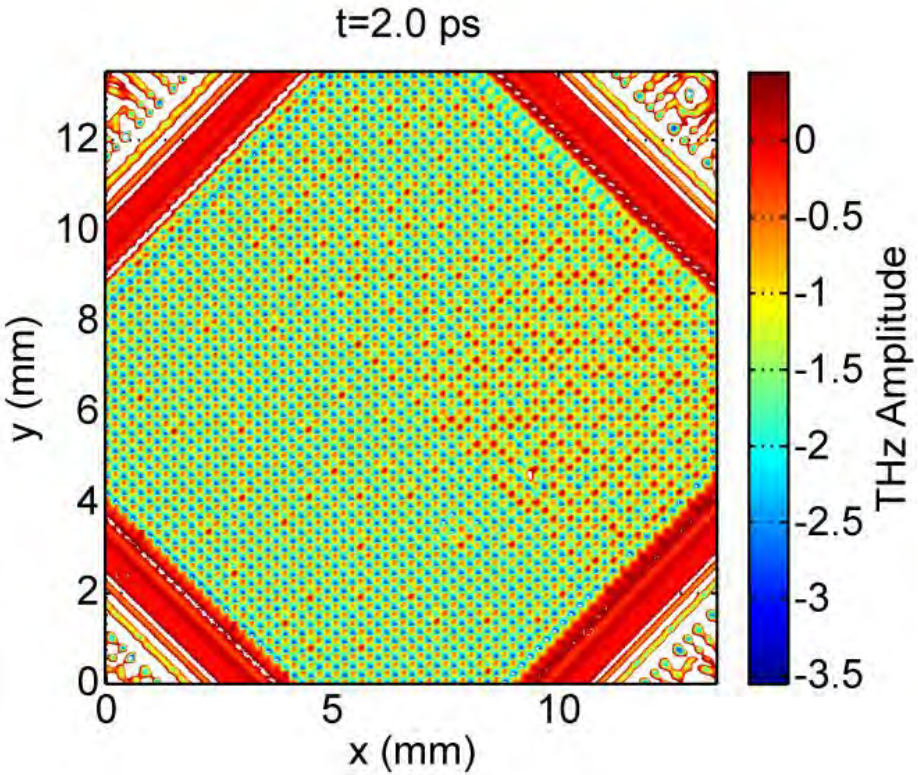
Metamaterials for sensing



Time-domain measurements

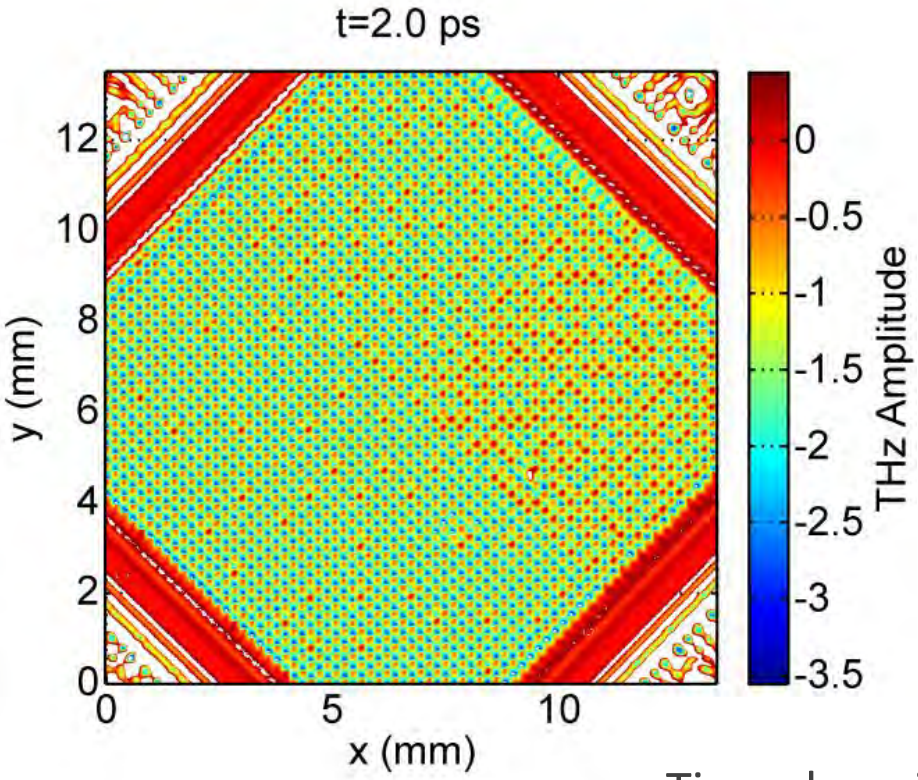
Metamaterials for sensing

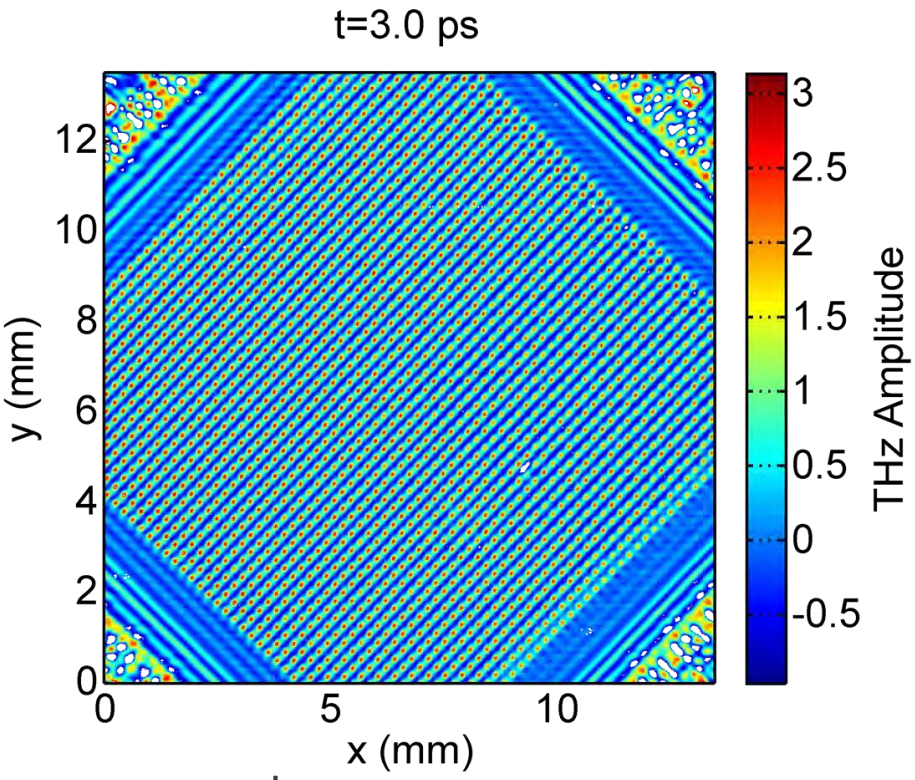




Time-domain measurements

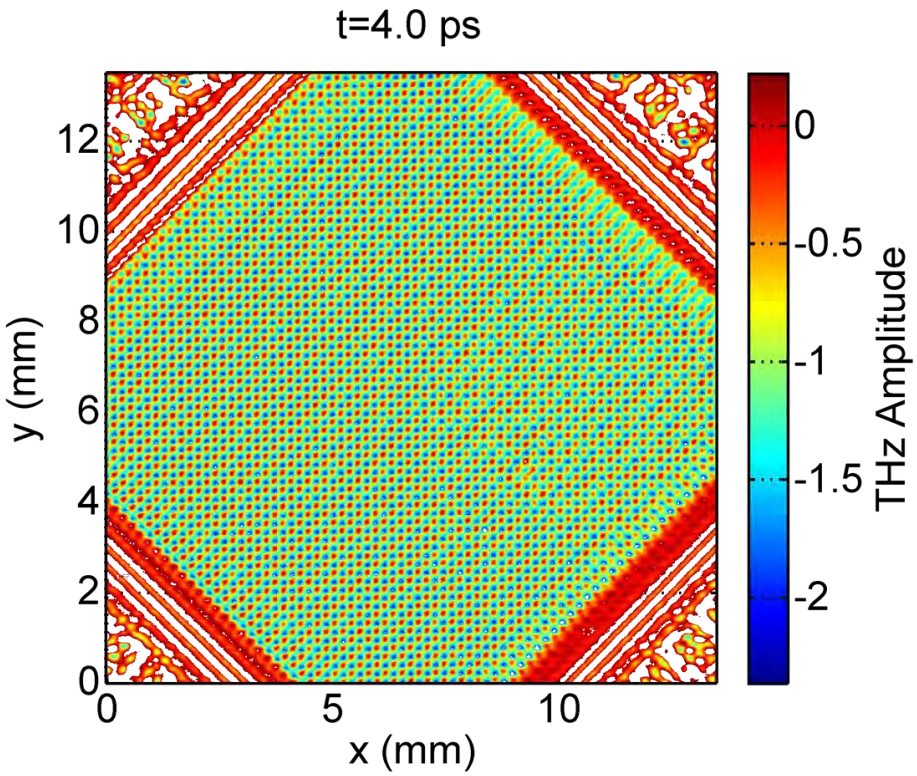
Metamaterials for sensing

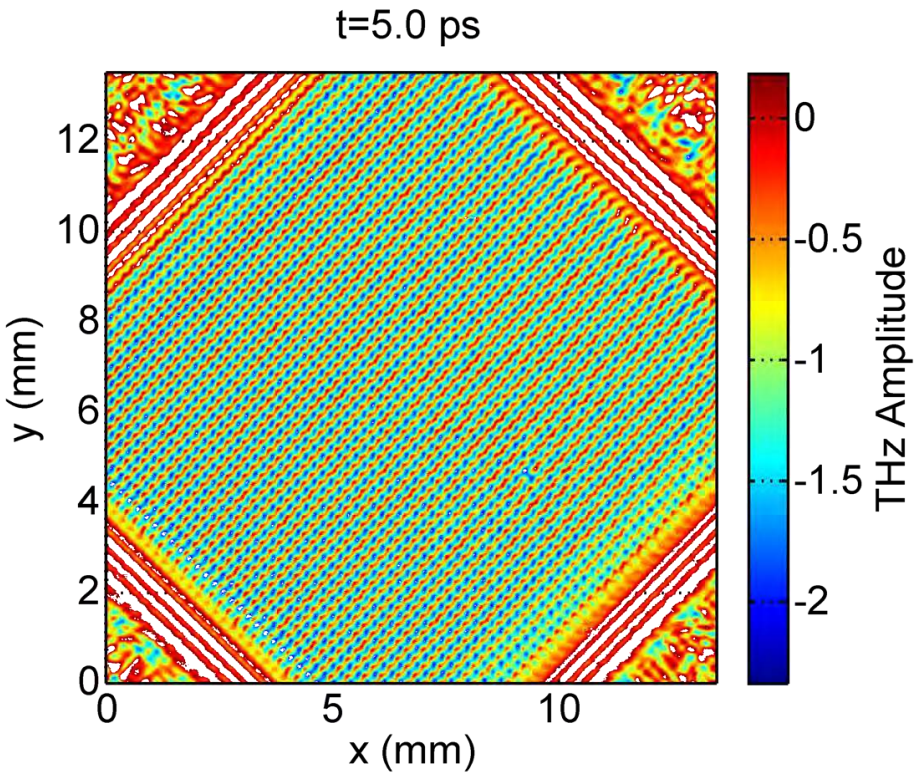




Time-domain measurements

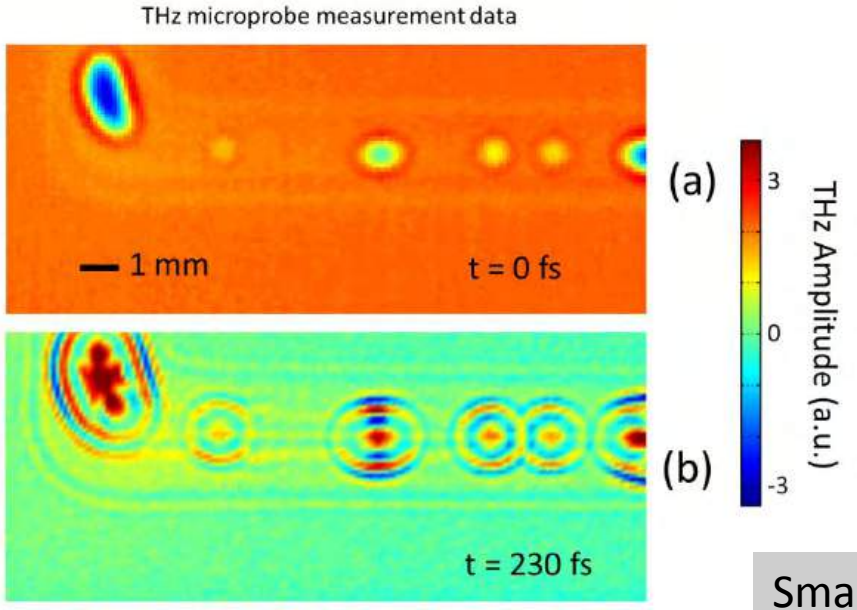
Metamaterials for sensing

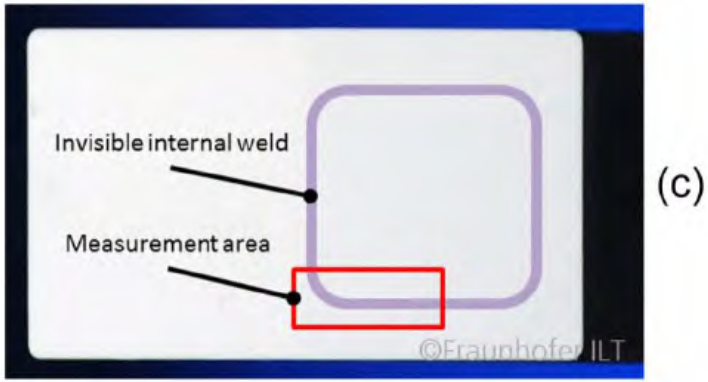




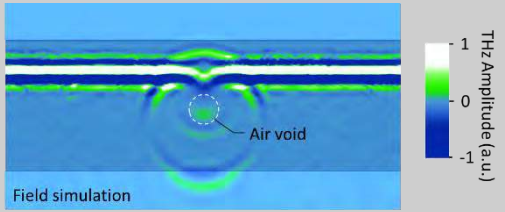
Time-domain measurements

Laser plastic weld inspection

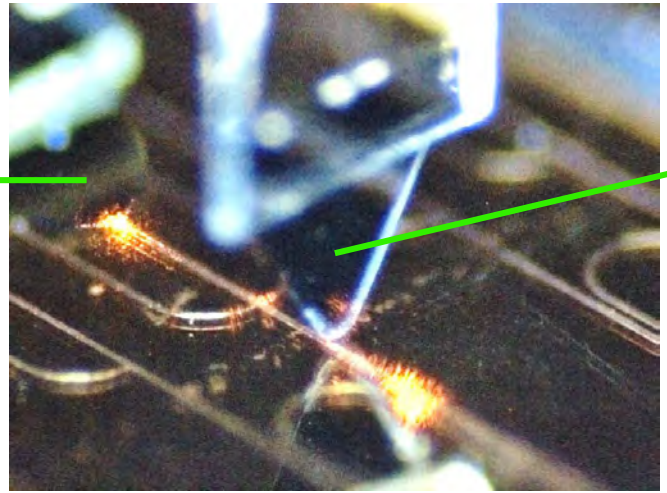




Small objects become visible by scattering light in the near-field:



THz on-chip analysis



On-chip pulse emitter tip

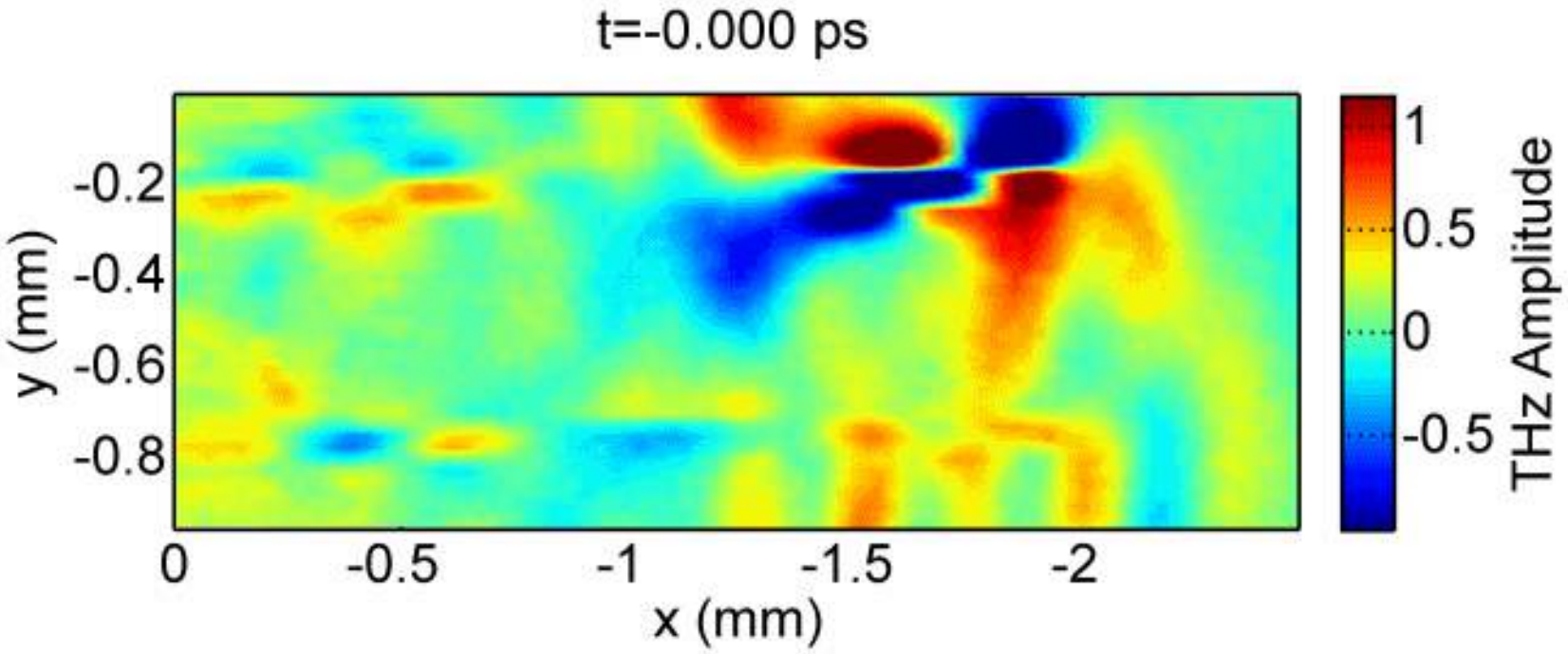
Near-field detector tip

Scanning area

30 µm

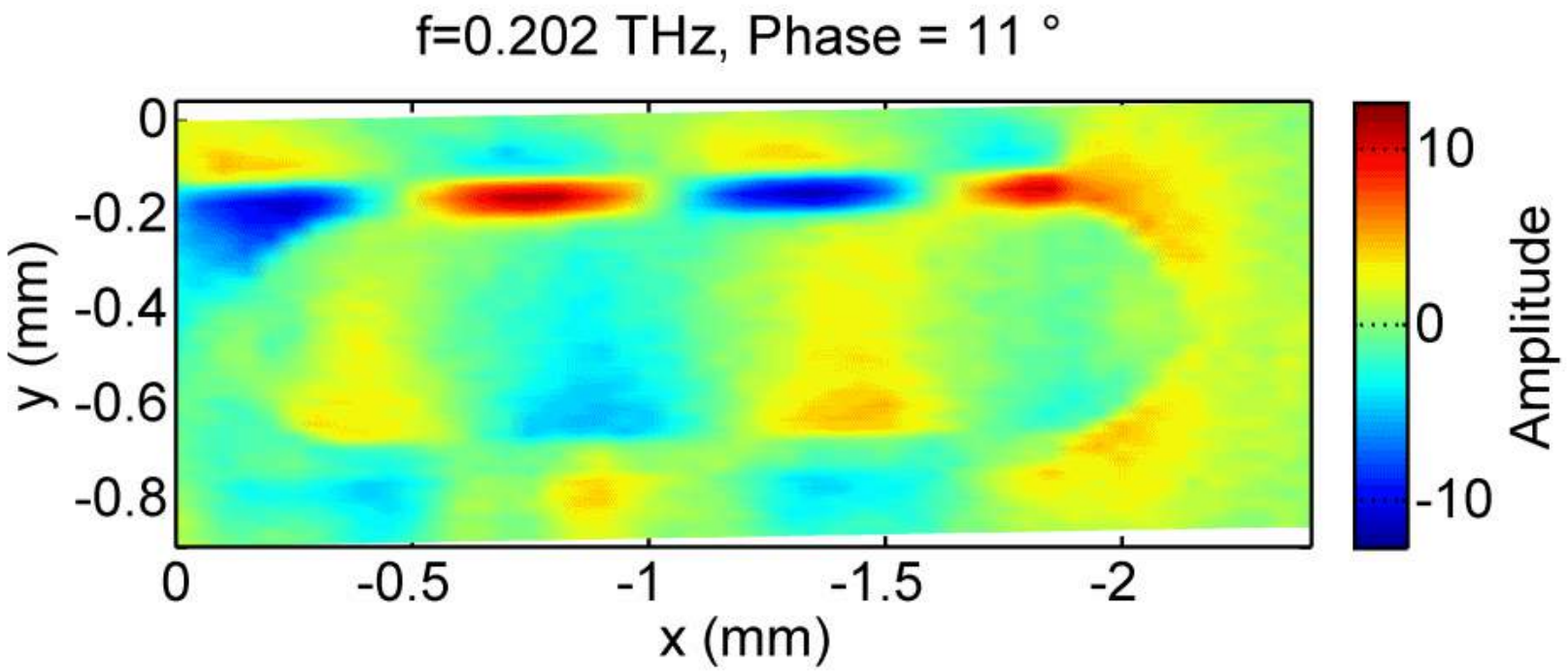
Thin-film microstripline

THz on-chip analysis



Time-domain measurement

THz on-chip analysis



Frequency-domain measurement data extraction

Failure localization

Failure localization → Target preparation → Failure analysis → Material characterization

Failure localization	Target preparation	Failure analysis	Material characterization
(non-destructive) LIT, **TDR**, X-ray, …	**(destructive)** Laser, FIB, RIE, wet chemistry, milling, abrasive blasting, ...	**(image defect & physical analysis)** SEM / EBSD, EDX, TEM, ToF-SIMS...	Image correlation, ESPI, …

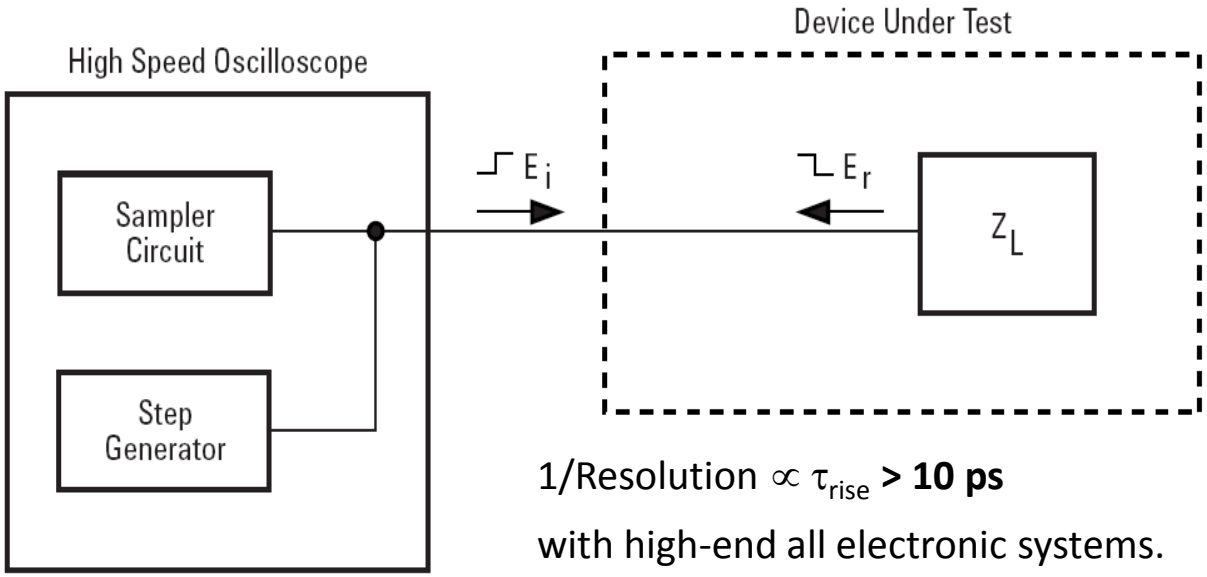
Limited accuracy/information but fast

Expensive & time consuming

Failure localization

Hewlett-Packard Journal,
“Time domain reflectometry“
June 1969, Vol. 20, No. 10

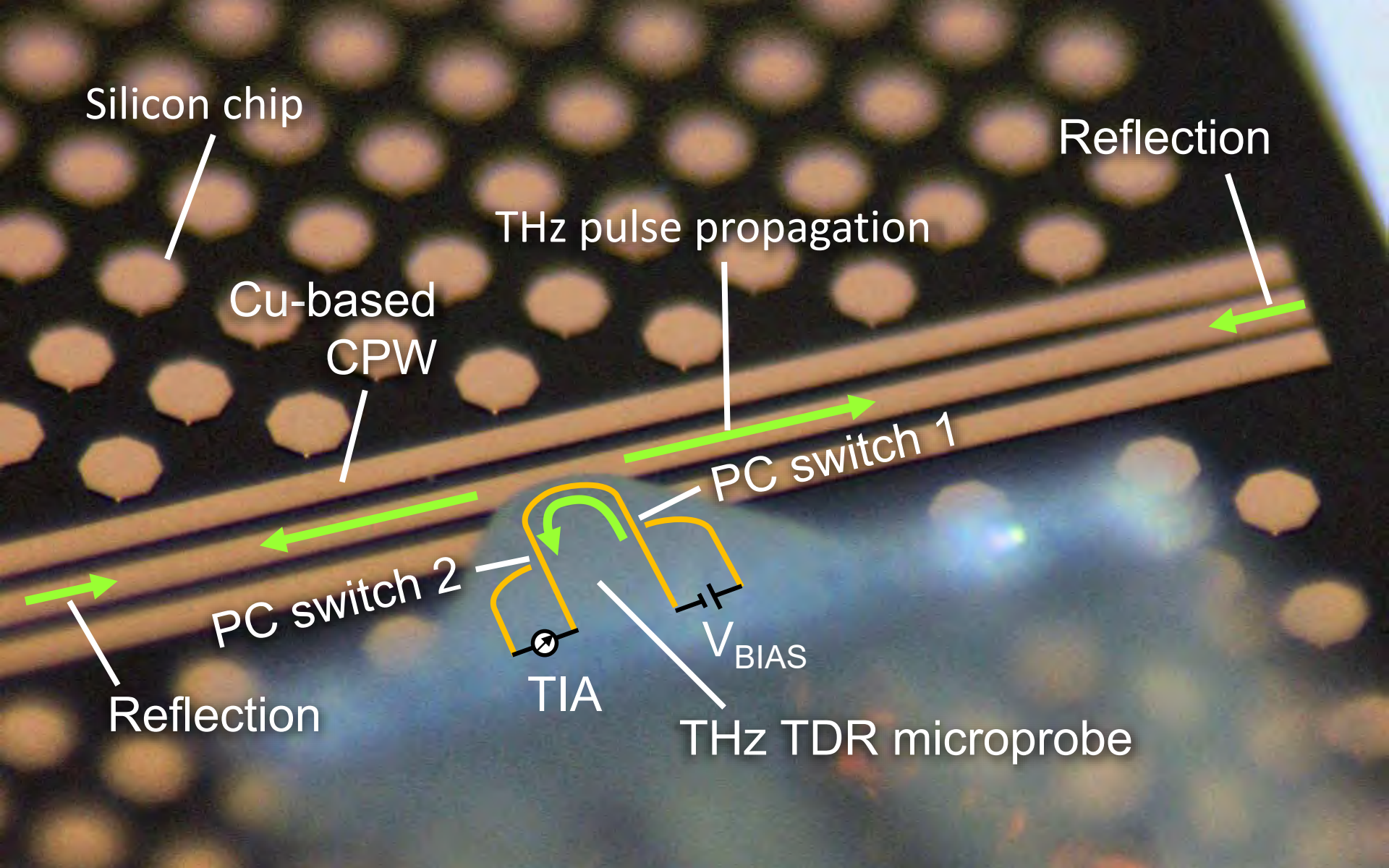
TDR principle scheme:



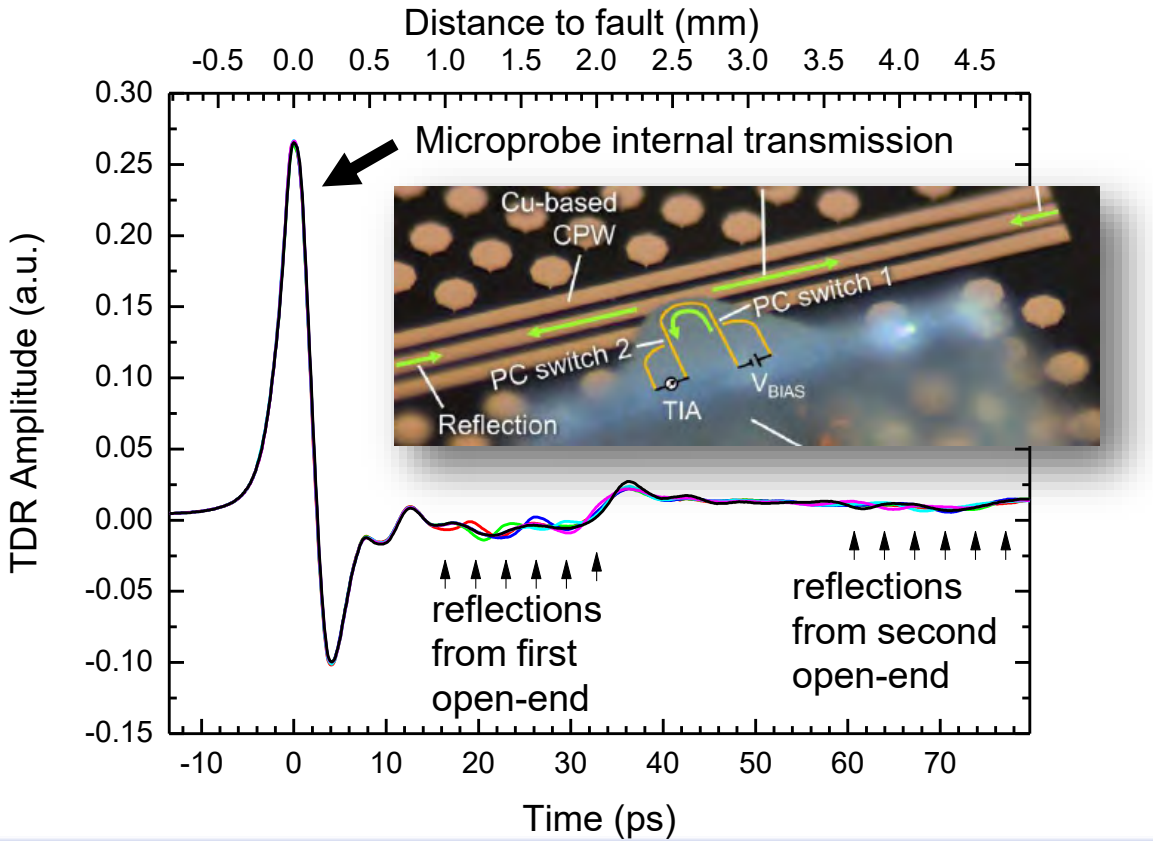
1/Resolution $\propto \tau_{rise}$ **> 10 ps**

with high-end all electronic systems.

Our Terahertz microprobes achieve up to sub-1 ps rise-times!

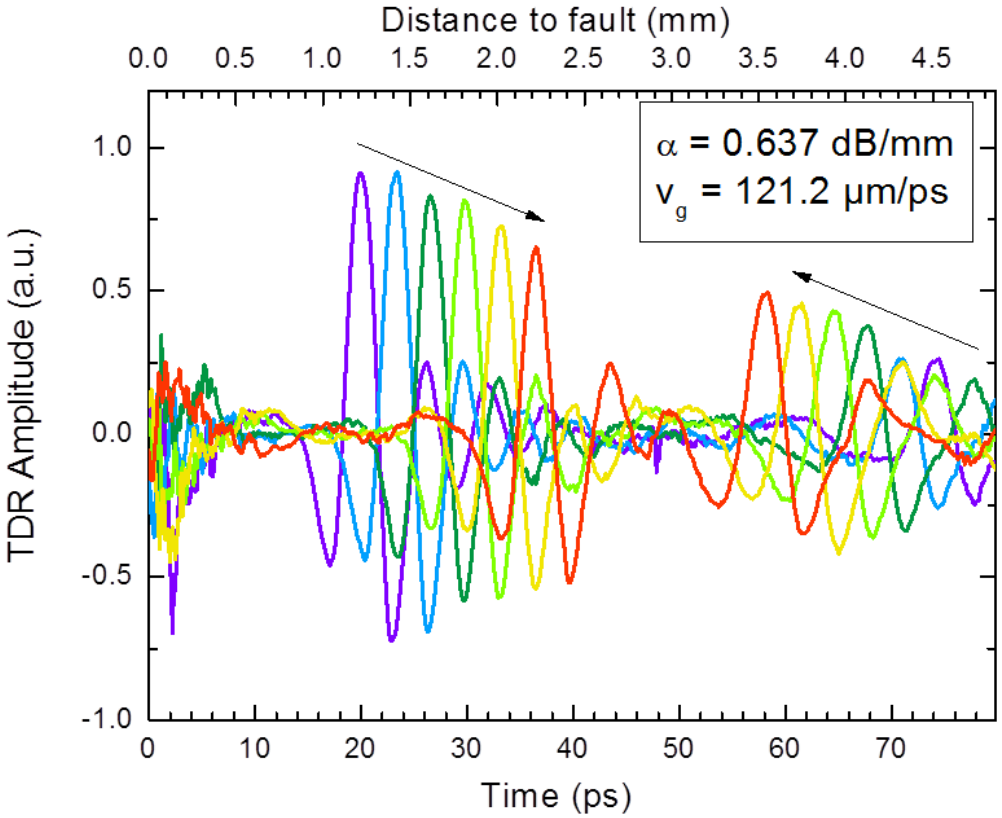

Silicon chip
Reflection
THz pulse propagation
Cu-based
CPW
PC switch 1
PC switch 2
Reflection
TIA
V_{BIAS}
THz TDR microprobe

Failure localization



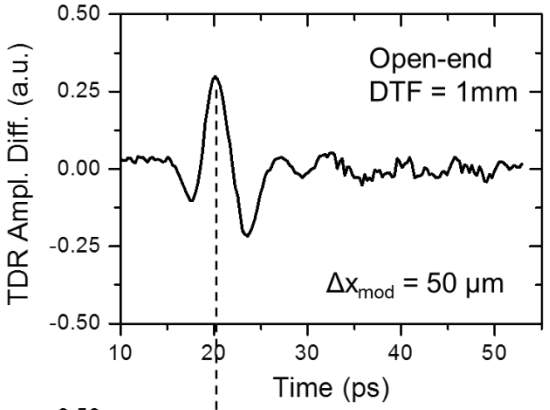
- Internal transmission as reference signal
- Multiple transient scans at different distances to fault
- Reflection signals from short and far distance opens

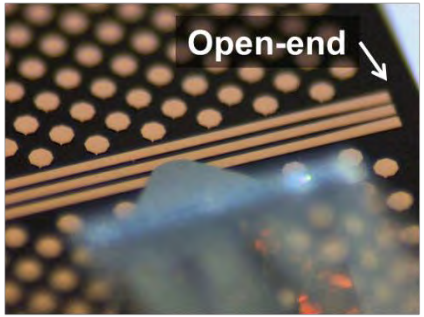
Failure localization

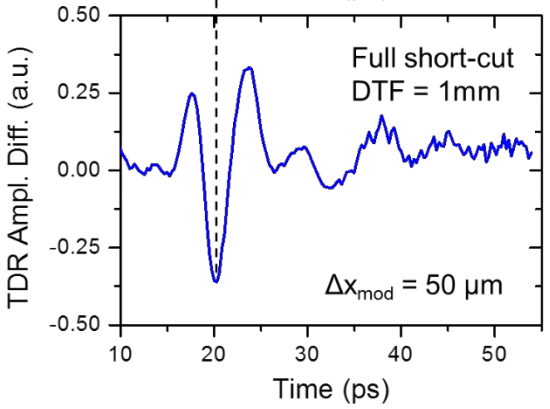


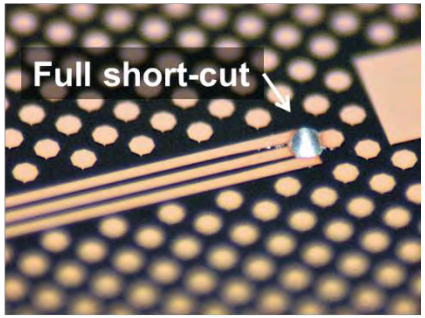
- Suppression of internal transmission signal through distance-to-fault modulation
- Determination of propagation dynamics:
  - Attenuation
  - Group/phase velocities

Failure localization



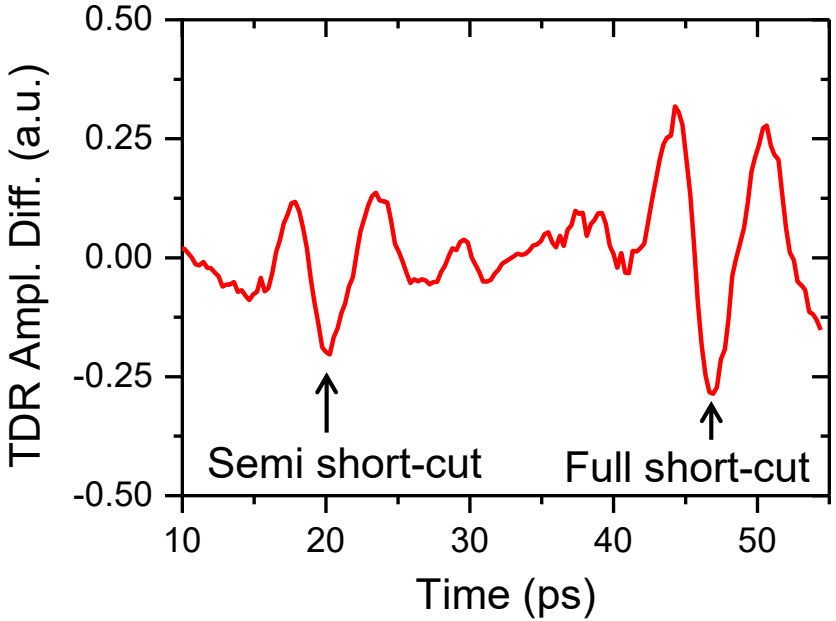


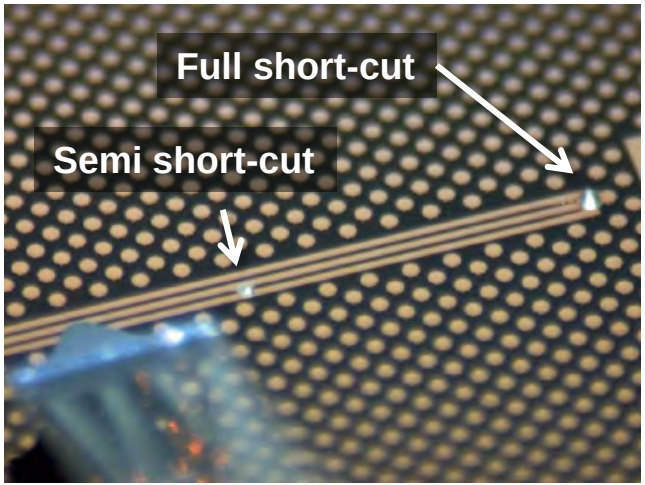




- Type of fault discremination
- Open vs. Short-cut
- Resistive faults
- Resonant faults

Failure localization



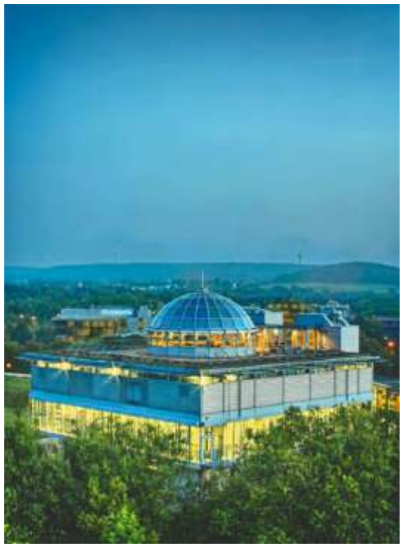


- Detection of consecutive faults

Conclusion

- **THz microprobes**
  - Efficient and versatile tools to avoid inefficient coupling of free-space THz radiation to micro/nanostructures
- **Examples: Surface analysis**
  - **Sheet resistance imaging**
    - Non-destructive (contactless), Fast (< 5ms/Pixel)
    - Quantitative (R_{sh} range: 0.1 – 10000 Ohm)
    - High resolution (ca. 10 µm)
  - **Metamaterial-based sensing**
    - Increased sensitivity through near-field single element read-out
- **Examples: THz device analysis**
  - **THz on-chip testing:** Access to field vector components, amplitude, phase, time- & frequency domain information
  - **Failure localization in chip packages:** > 10-times increased fault location resolution through sub-ps rise-time THz signals

Contact information



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